

In re application of

Confirmation No. 1092

Hiroto YUKAWA et al.

Attorney Docket No. 2004_0499

Serial No. 10/810,902

Group Art Unit 1752

Filed March 29, 2004

Examiner Sin J. Lee

POSITIVE-WORKING CHEMICAL-AMPLIFICATION PHOTORESIST

Mail Stop: AF

COMPOSITION

RESPONSE TO FINAL REJECTION

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In Response to the Final Rejection dated July 12, 2006, please amend the present application as follows: